

FIG. 1

0933363 0930930

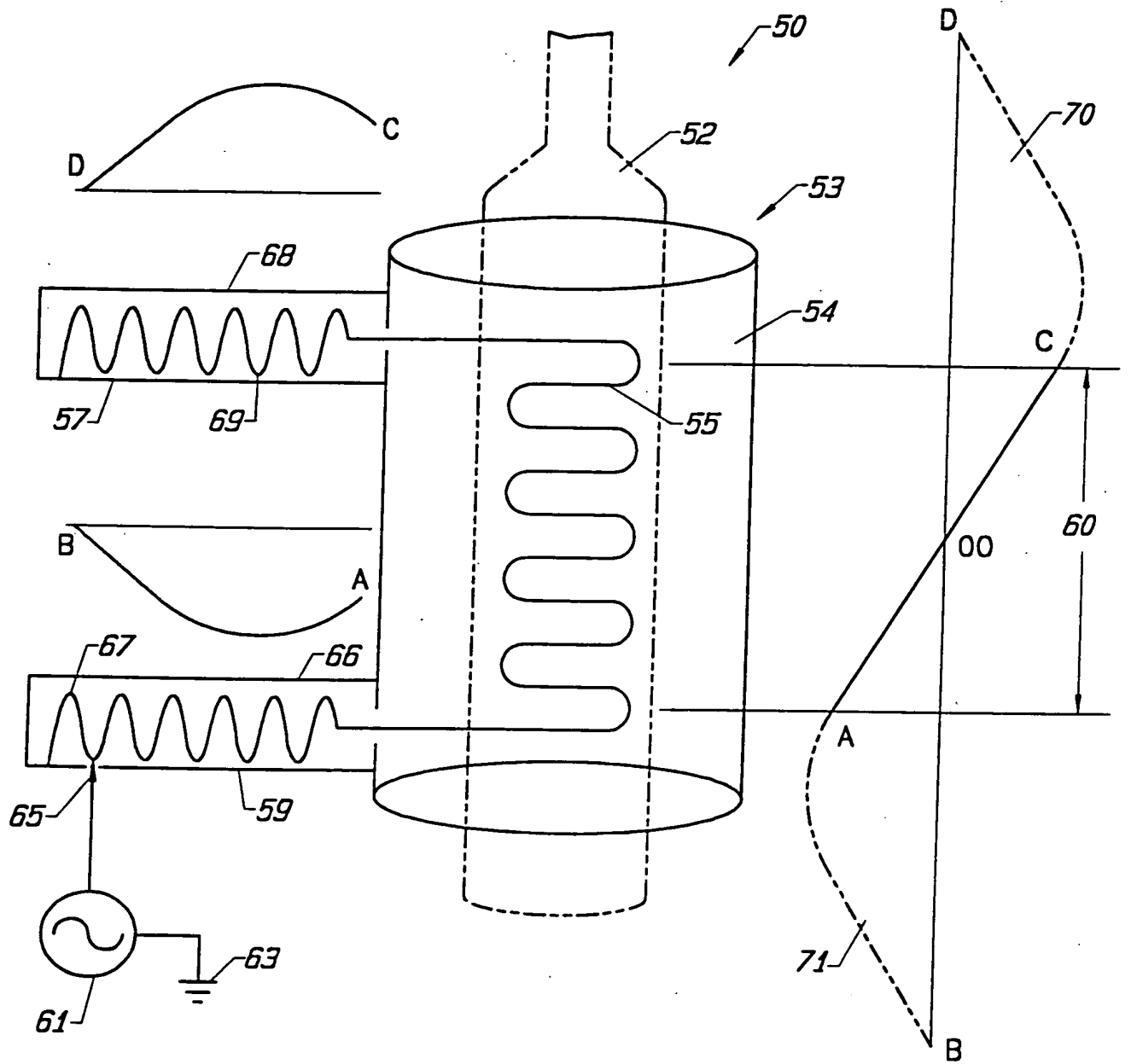


FIG. 2A

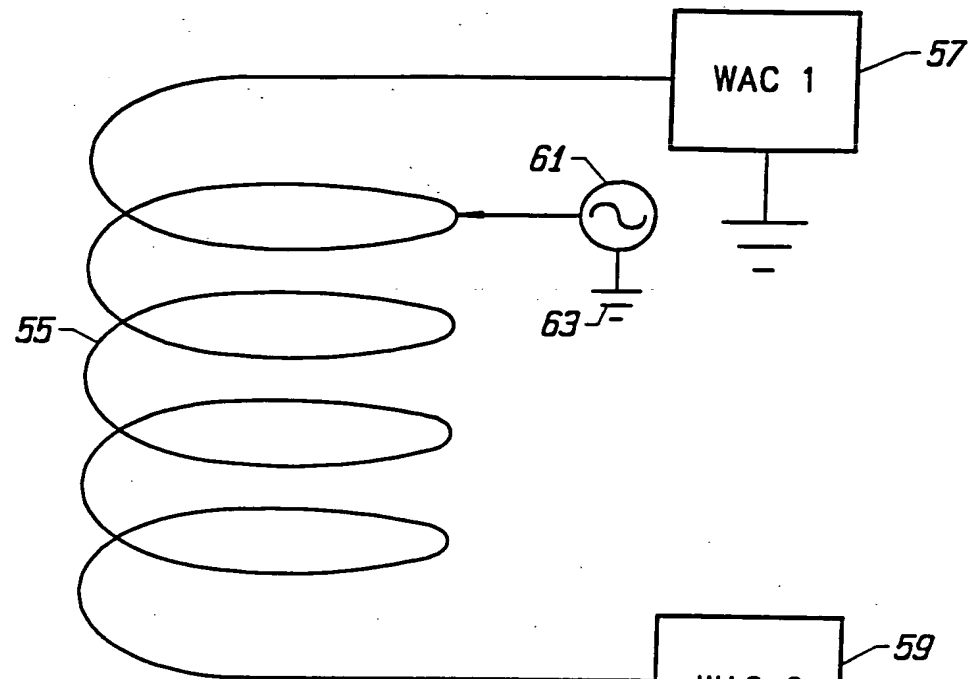


FIG. 2B

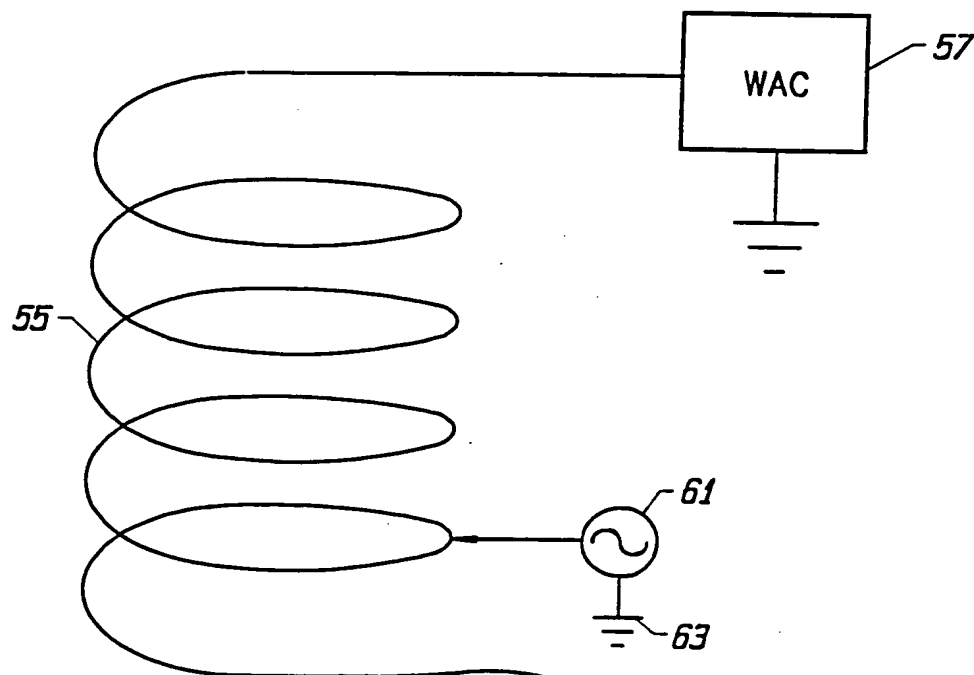


FIG. 2C

09331163, 09330936

09757763-097099

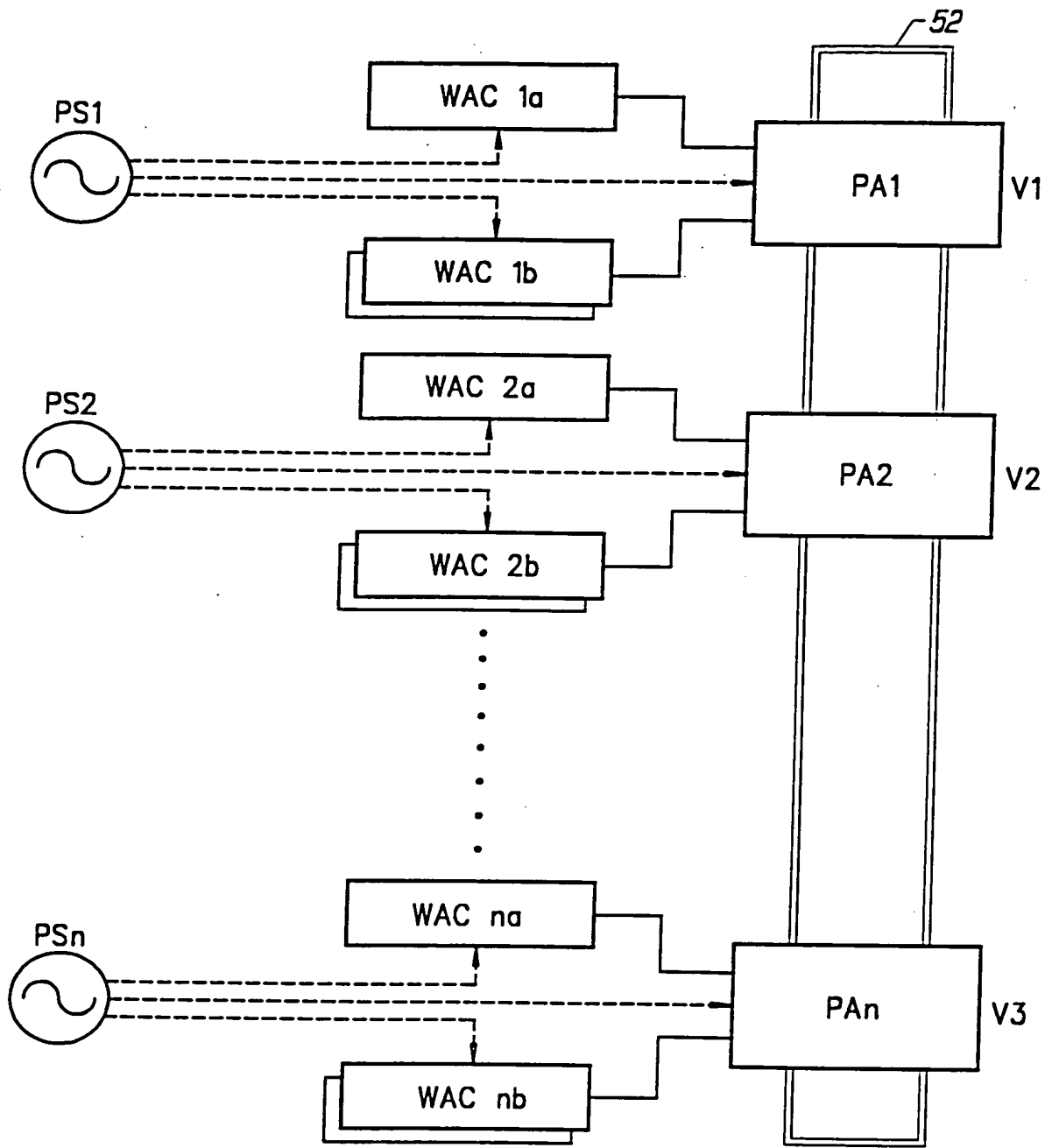


FIG. 2D

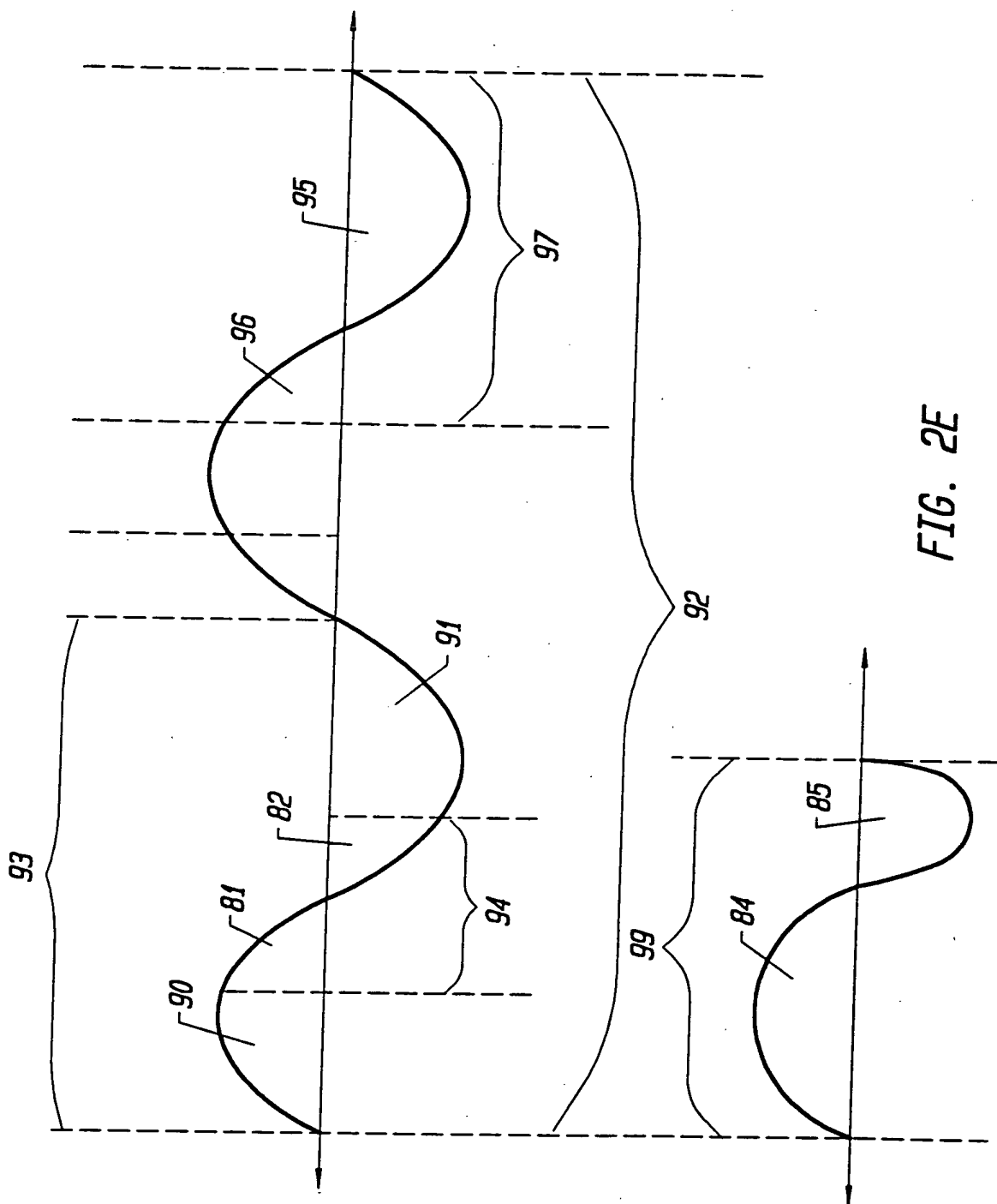


FIG. 2E

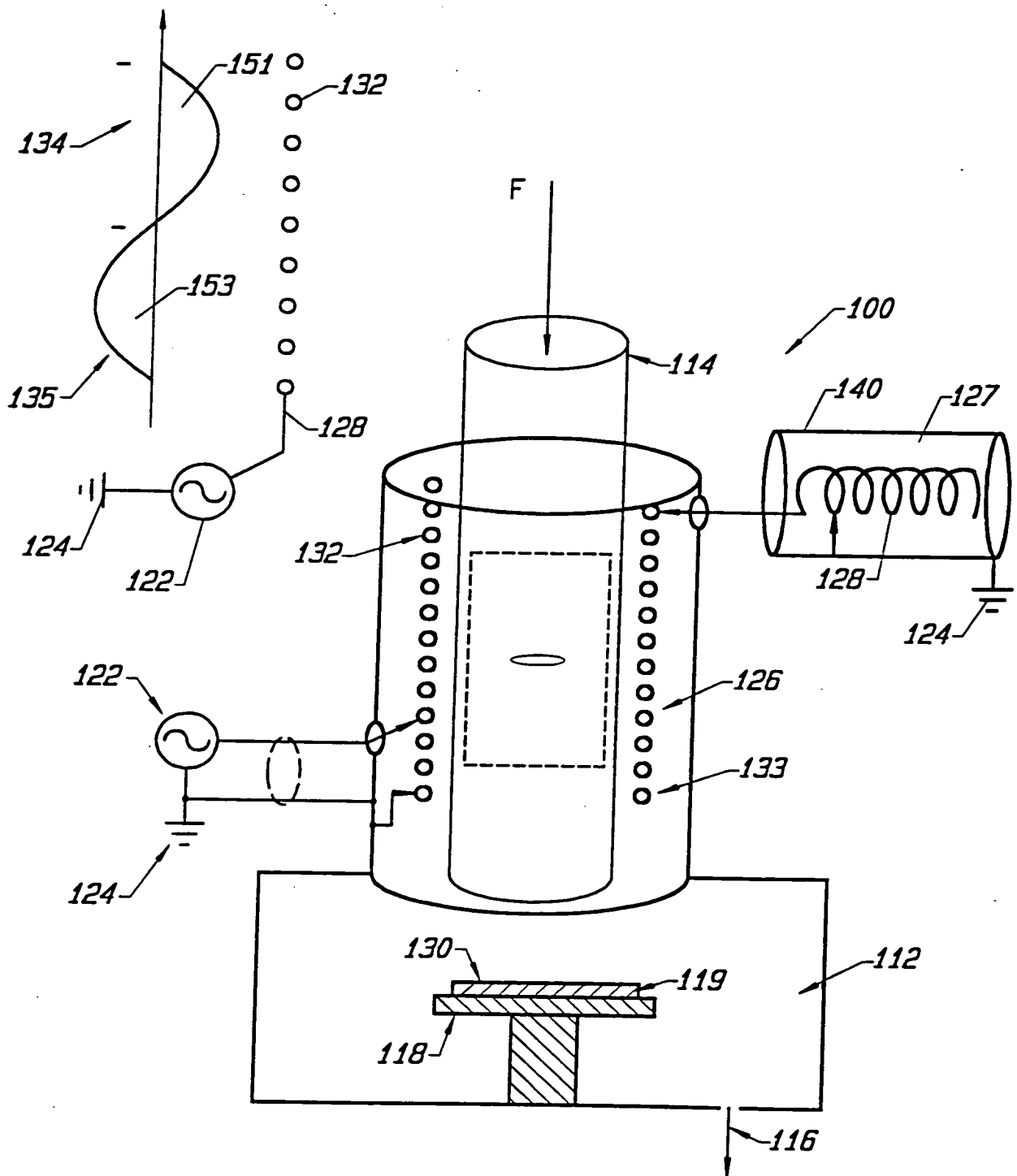


FIG. 3

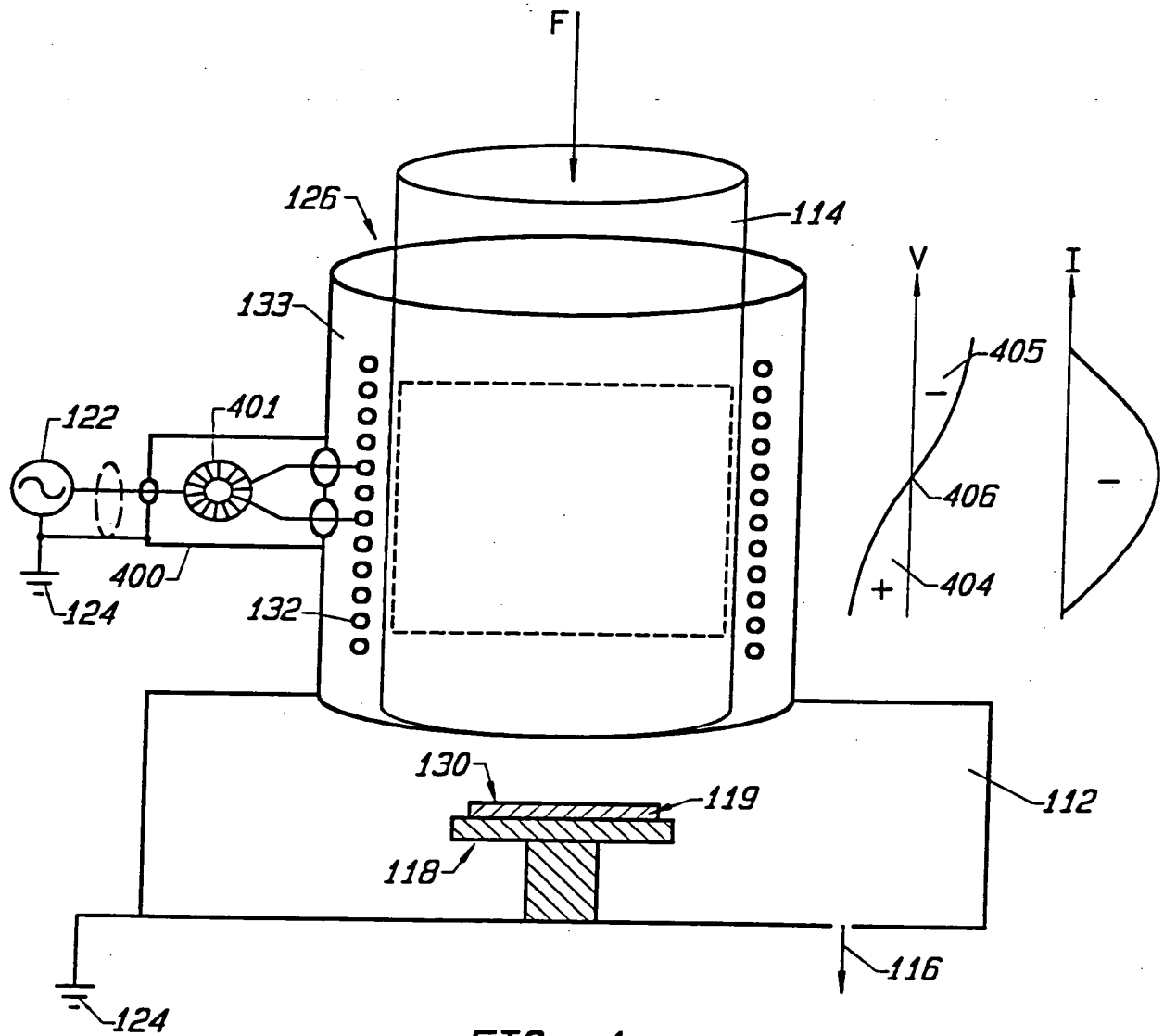


FIG. 4

09151163-097098

09351153-091093

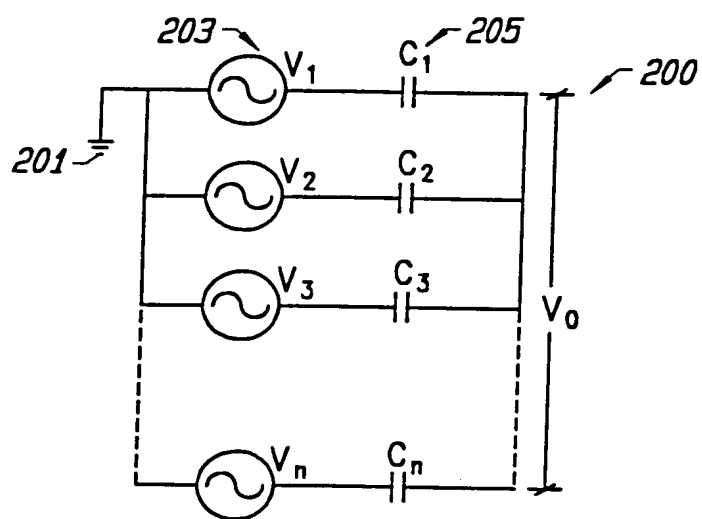


FIG. 5A

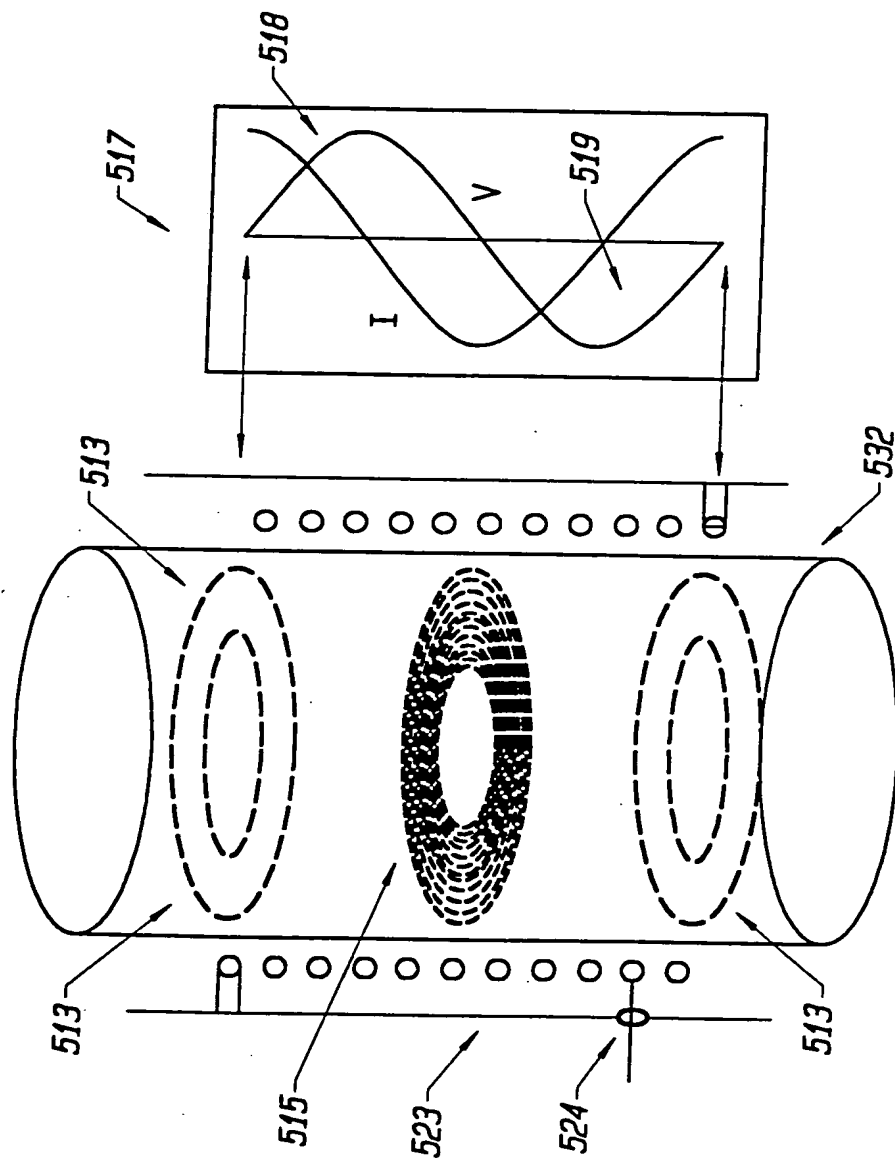
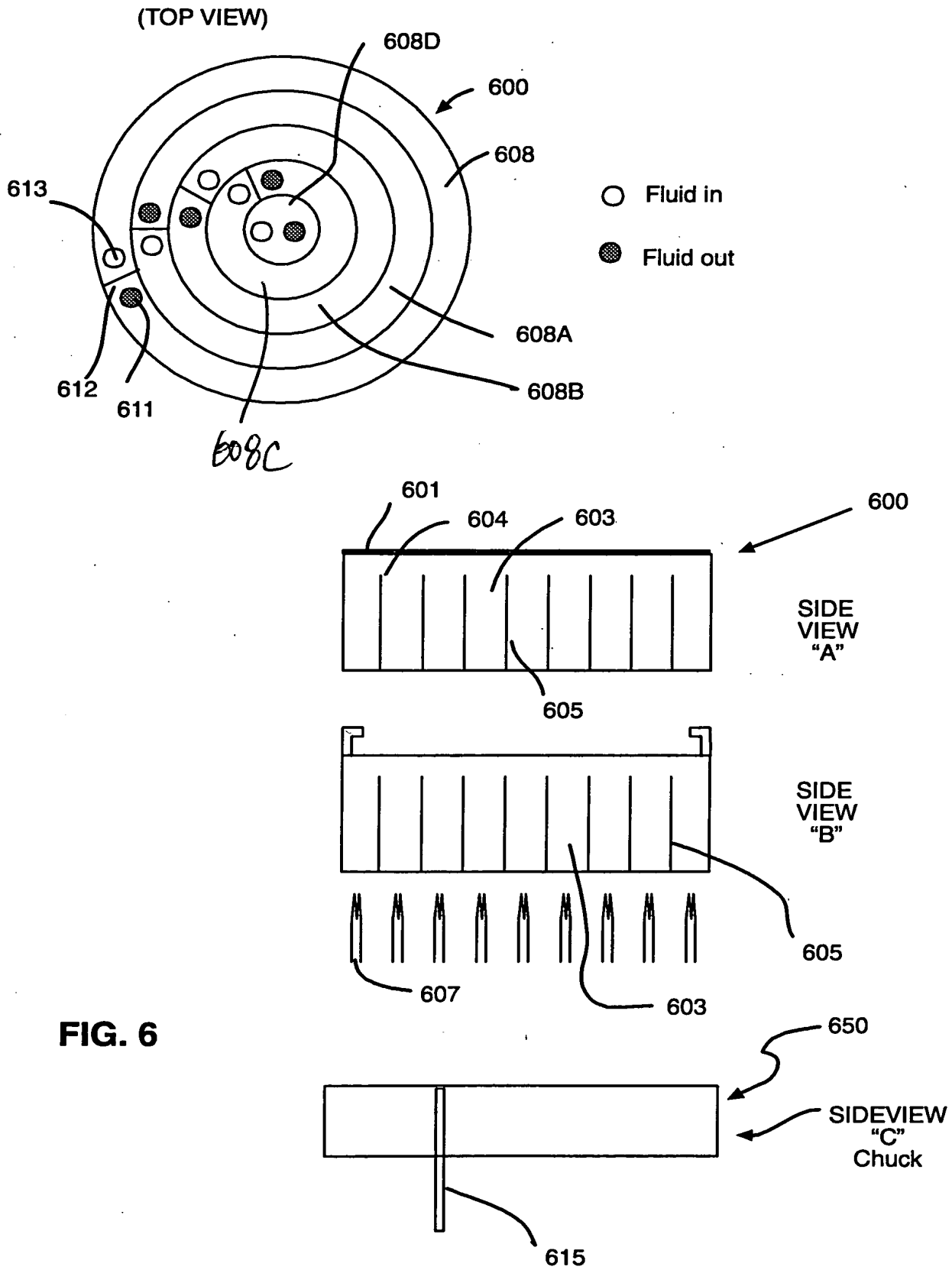


FIG. 5C

09157163.091093
950760" 89157163



09153163.091098

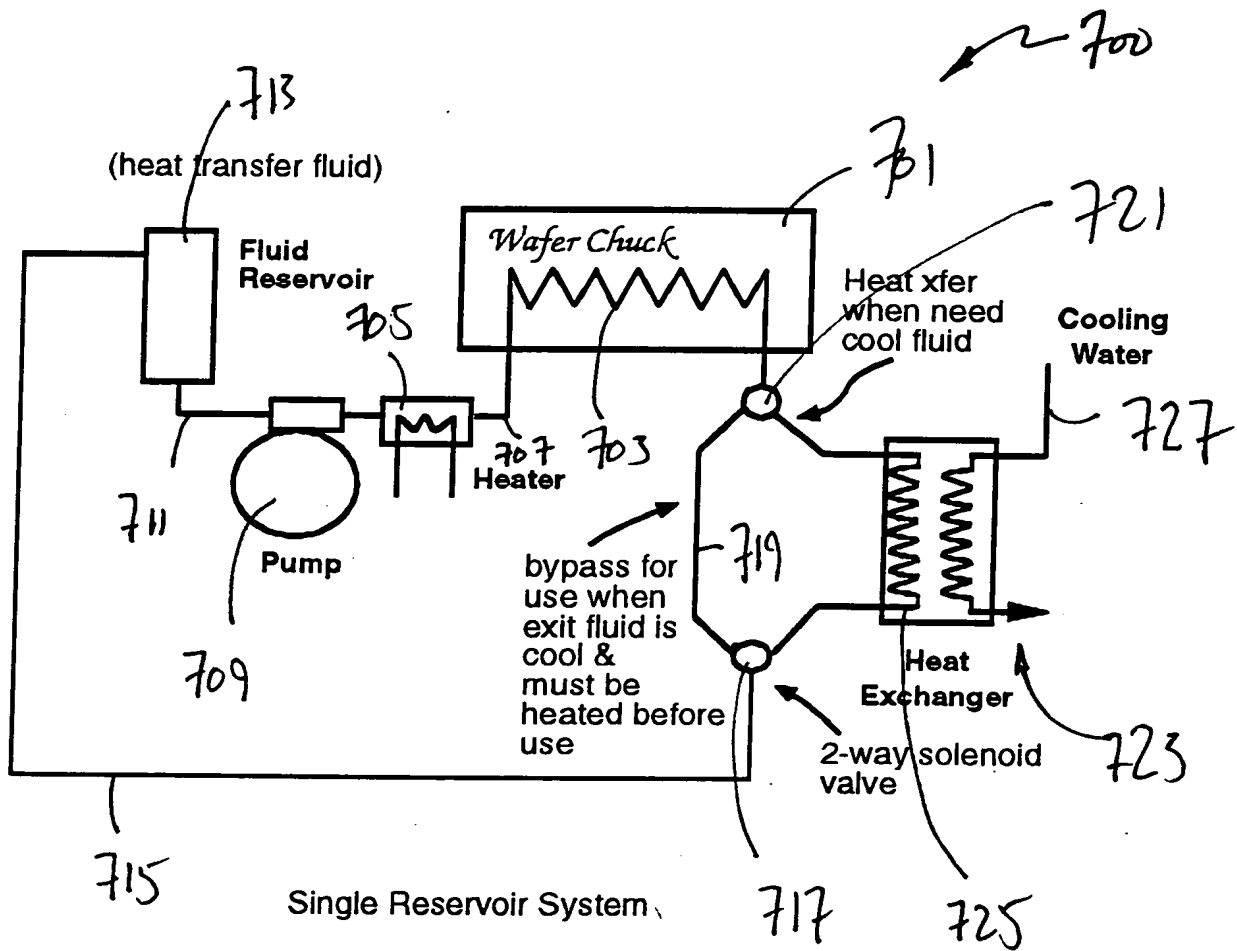


FIG. 7

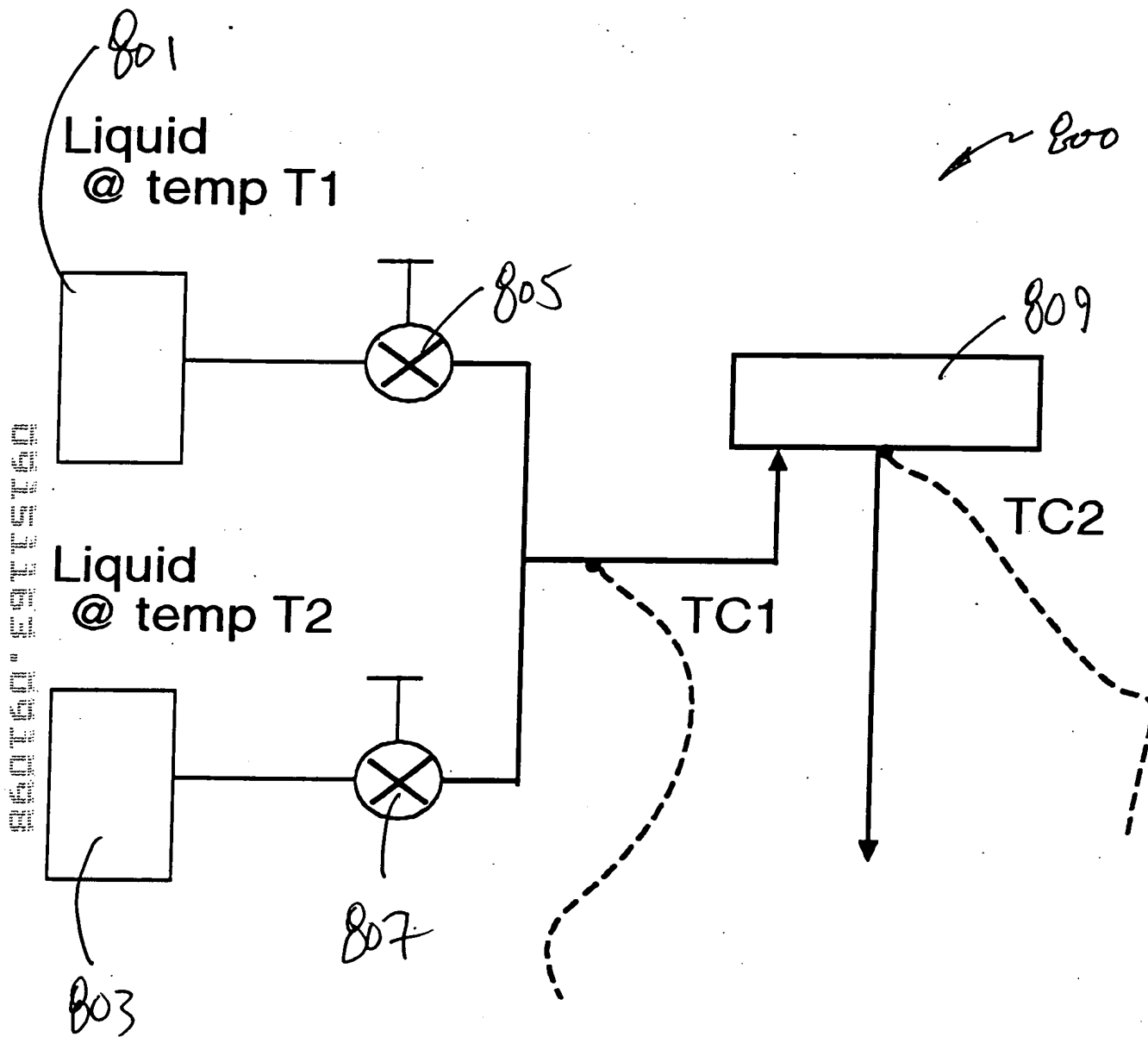


FIG. 8

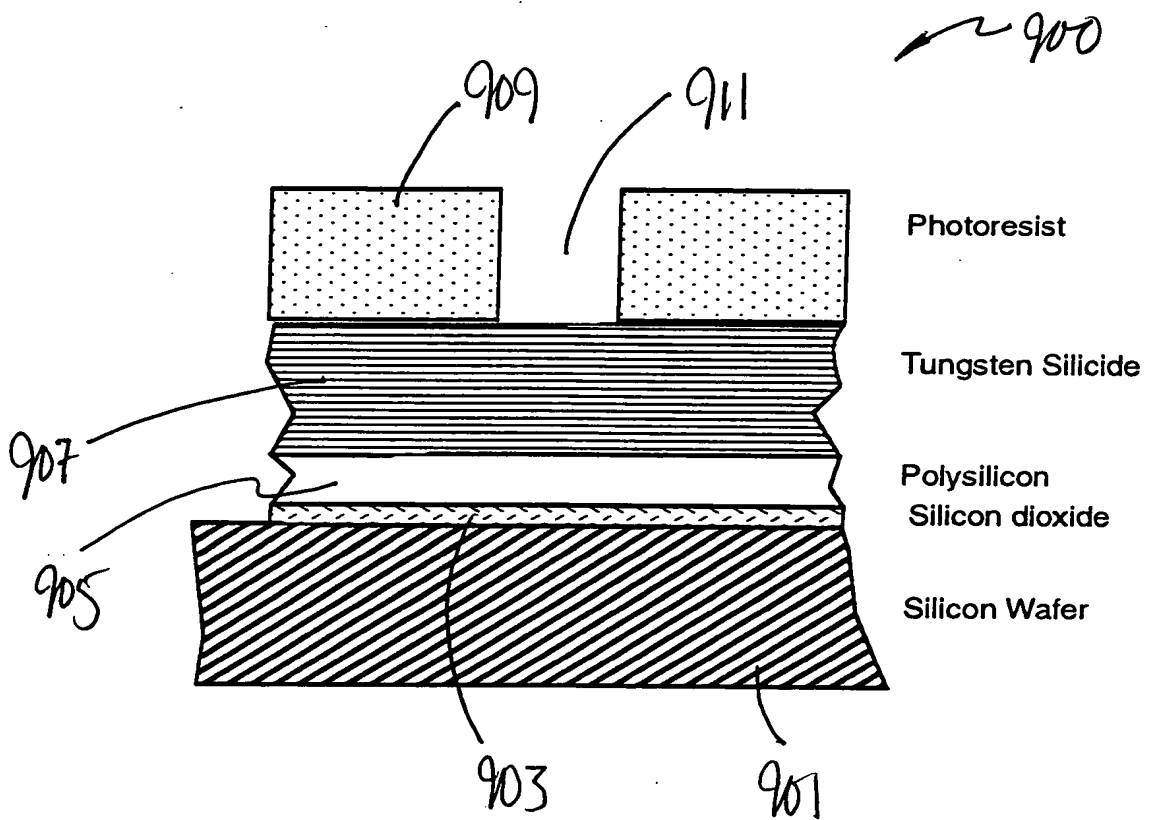
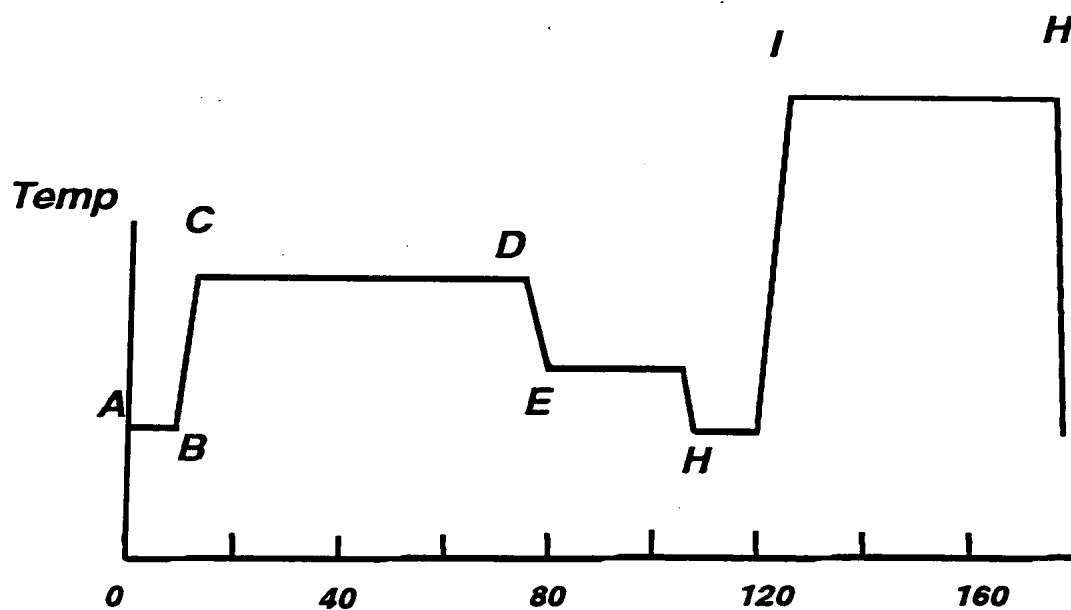
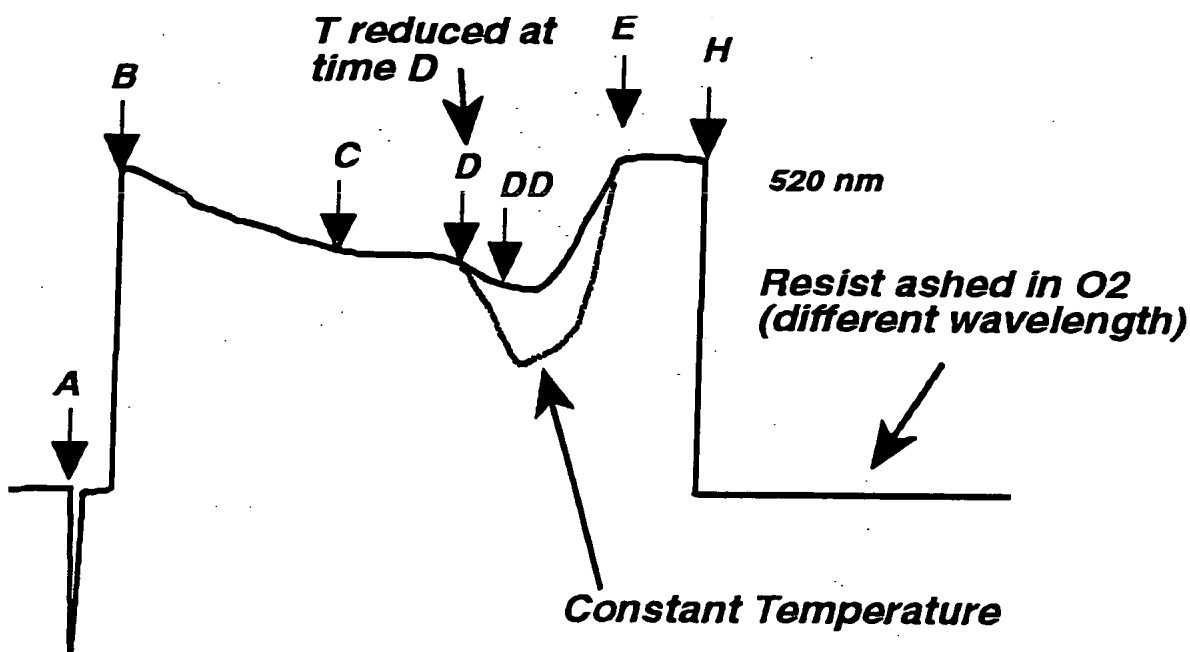


FIG. 9



- A. SF_6 native oxide "breakthrough"
- B. Cl_2 plasma is ignited
- C. WSi_x begins to clear (endpoint)
- D. Polysilicon is exposed
- E. Polysilicon cleared to oxide
- H. Plasma extinguished and O_2 feed gas flow is started
- I. O_2 plasma is started
- J. O_2 plasma is extinguished.

FIG. 10